

Title (en)

Apparatus for generating a negatively charged ionic reducing gas

Title (de)

Vorrichtung zur Erzeugung eines negativ geladenen reduzierenden Ionengases

Title (fr)

Appareil pour générer un gaz réducteur ionique à charge négative

Publication

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Application

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Priority

- EP 04010009 A 20040427
- US 42542603 A 20030428
- US 81922704 A 20040407

Abstract (en)

[origin: EP1473105A2] The present invention provides a method and apparatus for the dry fluxing of at least one component (25) and/or solder surface via electron attachment. In one embodiment, there is provided a method for removing oxides from the surface of a component (25) comprising: providing a component (25) on a substrate (24) wherein the substrate (25) is grounded or has a positive electrical potential to form a target assembly; passing a gas mixture (26) comprising a reducing gas through an ion generator (21) comprising a first and a second electrode; supplying an amount of voltage to at least one of the first and second electrodes sufficient to generate electrons wherein the electrons attach to at least a portion of the reducing gas and form a negatively charged reducing gas; and contacting the target assembly (24) with the negatively charged reducing gas to reduce the oxides on the component (25). <IMAGE>

IPC 8 full level

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US 6100496 A 20000808 - TAKUYA MIYAKAWA [JP], et al

Cited by

CN102928080A

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